

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Appln. Of: TANABE et al.

Serial No.: 09/612,551

Filed: July 7, 2000

For: SEMICONDUCTOR THIN FILM FORMING SYSTEM

Group: 1725

Examiner: EVANS, G.

DOCKET: NEC WNZ-2212

Assistant Commissioner of Patents and Trademarks
Washington, D.C. 20231

AMENDMENT B

Dear Sir:

The following amendment is being filed in response to the Official Action mailed December 3, 2001. A Petition for One Month Extension of Time accompanies this amendment.

Please amend the Application as follows:

IN THE SPECIFICATION:

Kindly cancel the present Specification, and insert in place thereof the attached new Specification.

IN THE CLAIMS:

Please amend Claim 1 to read as follows:

1. (Amended) A semiconductor thin film forming system for modifying a predetermined region of a semiconductor thin film by exposing the semiconductor thin film to a projected light patterned through plural patterns formed on a photo mask,

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